


Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it contains a valid OMB control number.

Substitute for form 1449B/PTO <b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>  Date Submitted: <b>AUG 2 2 2003</b> (use as many sheets as necessary)				<b>Complete if Known</b>	
				Application Number	Unassigned 2 2003
				Filing Date	AUG 2 2 2003
				First Named Inventor	Hisatsugu KURITA
				Group Art Unit	Unassigned
				Examiner Name	Unassigned
				Attorney Docket Number	047297-0137
Sheet	1	of	1		

U.S. PATENT DOCUMENTS						
Examiner Initials*	Cite No. <sup>1</sup>	U.S. Patent Document		Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number	Kind Code <sup>2</sup> (if known)			

FOREIGN PATENT DOCUMENTS								
Examiner Initials*	Cite No. <sup>1</sup>	Foreign Patent Document			Name of Patentee or Applicant of Cited Documents	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T <sup>6</sup>
		Office <sup>3</sup>	Number <sup>4</sup>	Kind Code <sup>5</sup> (if known)				
MK	A1	JP	10-340876	A	SHIBAURA ENG WORKS CO., LTD.	12-22-1998		✓

NON PATENT LITERATURE DOCUMENTS				
Examiner Initials*	Cite No. <sup>1</sup>	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.) date, page(s), volume-issue number(s), publisher, city and/or country where published.		T <sup>6</sup>
MK	A2	S. VERHAVERBEKE et al., "THE EFFECT OF H <sub>2</sub> ANNEALING ON THE SI SURFACE AND ITS USE IN THE STUDY OF ROUGHENING DURING WET CHEMICAL CLEANING", Semiconductor Silicon, 1994, pages 1170-1181, vol. 94-no. 10, The Electrochemical Society, Inc.		
MK	A3	Y. YANASE et al., "AFM OBSERVATION OF Si(100) SURFACE AFTER HYDROGEN ANNEALING AND WET CHEMICAL PROCESSING", Electrochemical Society 184 <sup>th</sup> Meeting, Third international symposium on Cleaning Technology in Semiconductor Device Manufacturing, Oct. 10-15, 1993, 8 pages		

Examiner Signature		Date Considered	03/03/05
-----------------------	---	--------------------	----------

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

<sup>1</sup> Unique citation designation number. <sup>2</sup> See attached Kinds of U.S. Patent Documents. <sup>3</sup> Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). <sup>4</sup> For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document.

<sup>5</sup> Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. <sup>6</sup> Applicant is to place a check mark here if English language Translation is attached.

Burden Hour Statement: This form is estimated to take 2.0 hours to complete. Time will vary depending upon the needs of the individual case. Any comments on the amount of time you are required to complete this form should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, PO Box 1450, Alexandria, Virginia 22313-1450. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Commissioner for Patents, PO Box 1450, Alexandria, Virginia 22313-1450.